

5. (amended) A photoresist of claim 2 wherein the resin comprises a photoacid-labile ester group.

B3 6. (amended) A photoresist of claim 1 wherein the resin comprises a polymerized cyclic olefin.

7. (amended) A photoresist of claim 1 wherein the resin comprises a polymerized monomer comprising ethylene unsaturated carbonyl or di-carbonyl.

8. (amended) A photoresist of claim 1 wherein the resin is a terpolymer.

9. (amended) A photoresist of any one of claim 1 wherein the resin is a tetrapolymer.

10. (amended) The photoresist of claim 1 wherein the polymer further comprises one or more units selected from the group consisting of an acid; nitrile; an anhydride; a lactone; or a photoacid labile group that contains a leaving group that has other than an alicyclic moiety.

11. (amended) The photoresist of claim 1 wherein the polymer is substantially of aromatic groups.

12. (amended) A method of forming a positive photoresist relief image, comprising:

- (a) applying a coating layer of a photoresist of claim 1 on a substrate; and
- (b) exposing and developing the photoresist layer to yield a relief image.